
**Surface chemical analysis —
Secondary ion mass spectrometry
— Method for determining yield
volume in argon cluster sputter depth
profiling of organic materials**

Analyse chimique des surfaces — Spectrométrie de masse des ions secondaires — Méthode de détermination du rendement volumique dans le cadre du profilage en profondeur de matériaux organiques par pulvérisation d'argon en grappe





COPYRIGHT PROTECTED DOCUMENT

© ISO 2019

All rights reserved. Unless otherwise specified, or required in the context of its implementation, no part of this publication may be reproduced or utilized otherwise in any form or by any means, electronic or mechanical, including photocopying, or posting on the internet or an intranet, without prior written permission. Permission can be requested from either ISO at the address below or ISO's member body in the country of the requester.

ISO copyright office
CP 401 • Ch. de Blandonnet 8
CH-1214 Vernier, Geneva
Phone: +41 22 749 01 11
Fax: +41 22 749 09 47
Email: copyright@iso.org
Website: www.iso.org

Published in Switzerland